

ABSTRACT**EXPOSURE METHOD AND EXPOSURE APPARATUS, AND
DEVICE MANUFACTURING METHOD**

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When exposure is performed on the same substrate a plurality of times, the control system changes the control factor of the exposure system contributing to throughput, in accordance with the exposure accuracy required on each exposure.

10 For example, when the exposure accuracy required is high, the control factor is changed to a state (or a value) in which importance is put on resolution rather than throughput, and when the exposure accuracy required is moderate, then the control factor is changed so that priority is put on throughput.

15 Accordingly, compared with the case of controlling the exposure system using the same control factor on each exposure, throughput can obviously be improved. In addition, the control factor is changed to a state (or a value) in which importance is put on throughput, only when the exposure accuracy required

20 is moderate, thus, the exposure accuracy can be sufficiently maintained.

Fig. 1

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